

1/f noise in GaAs: Evidence of a new scale invariance

P. J. Restle, M. B. Weissman, and G. A. Garfunkel

*Department of Physics, University of Illinois at Urbana-Champaign,
1110 West Green Street, Urbana, Illinois 61801*

P. Pearah and H. Morkoç

*Coordinated Science Laboratory, University of Illinois at Urbana-Champaign,
Urbana, Illinois 61801*

(Received 12 May 1986)

Low-frequency noise measurements were made in the temperature range of 77–340 K on sub-micrometer resistors made from GaAs grown by molecular-beam epitaxy. Two types of noise were found, depending on surface treatment. One type consisted of discrete spectral components which showed no anomalous statistical behavior. The other type was a small 1/f component which showed anomalously large variations in spectral density, with these variations themselves having a 1/f spectrum.

For many years there have been two general approaches to the question of the origins of 1/f noise and other strongly nonexponential relaxation and fluctuation phenomena. One approach is to look for some reason for a set of parallel processes, which individually have exponential kinetics, to have the necessary distribution of characteristic rates.^{1–3} The other approach is to look for a set of processes whose kinetics occur in a series, with the form of the linkage between the fast and slow processes determining the overall kinetic form.^{4–7} Although these two approaches can each predict the principle forms of nonexponential kinetics if suitable assumptions are made, they lead to very different predictions for the behavior of systems small enough to allow measurements either of individual transitions^{8,9} or of nontrivial statistical properties in the fluctuations other than the ordinary power spectrum.^{10,11} In this paper we report evidence that 1/f noise in submicron GaAs resistors, unlike 1/f noise in several other systems,^{10,11} shows statistical properties inconsistent with parallel kinetic models.

We observed two types of noise in our samples. One consisted of a set of discrete spectral components whose properties were entirely consistent with a model of a superposition of two-state processes, such as carrier trapping. When this noise was mostly removed by surface treatment, a small amount of 1/f noise with unusual statistical properties remained. (See Fig. 1.) Although the 1/f noise is our topic we will also briefly describe the discrete noise, described in much more detail elsewhere.¹²

The GaAs was grown by molecular-beam epitaxy on a chrome-doped GaAs substrate. On a typical sample, a 0.5- μm buffer layer of undoped GaAs was grown followed by an 0.15- μm layer of GaAs doped with Si at $n = 7 \times 10^{17} \text{ cm}^{-3}$. Hall measurements were performed on samples from this wafer and yielded a mobility μ of $2780 \pm 50 \text{ cm}^2/\text{V sec}$ and a carrier density n of $(7 \pm 0.4) \times 10^{17} \text{ cm}^{-3}$ at 300 K; and $\mu = 2640 \pm 50 \text{ cm}^2/\text{V sec}$, $n = (7 \pm 0.4) \times 10^{17} \text{ cm}^{-3}$ at 77 K. Noise sample GaAs No. 1 was prepared using a single chrome mask with an anisotropic etch $[8(\text{H}_2\text{O}_2):1(\text{H}_2\text{SO}_4)]$. The first few attempts resulted in invisibly cracked central regions, so the wafer was

oriented to produce a central region having a wider base than top for structural stability.

In an attempt to make a smaller sample, a mask was made by scratching a randomly discontinuous line approximately 1 μm wide very lightly through the chrome of a chrome mask with a diamond scribe a number of times with different pressures, then using this as a mask with positive photoresist to generate another chrome mask (on unscratched glass with good optical properties) using a range of exposure times. This mask was used on GaAs wafers with a Shipley AZ 1450 positive photoresist, followed with the more isotropic etch $[1(\text{H}_2\text{O}_2):3(\text{NH}_4\text{OH}):15(\text{H}_2\text{O})]$ to etch a discontinuous "dotted-line" pattern. Another photoresist and etch process was then used to select one of the ~ 100 parallel resistors created by the dotted-line mask. Both processes resulted in samples with noise-generating regions having surface areas of $\sim 1 \mu\text{m}^2$ and containing $\sim 10^3$ carriers.

Annealed tin contacts were used that resulted in Ohmic, quiet, problem-free, and mechanically strong electrical contacts. Details of the annealing procedure are described elsewhere.¹²

As discussed below, a commercial positive photoresist developer consisting of a NaOH solution (Micro-Posit 451 developer) was later used as a slow high-quality GaAs etch to reduce the thickness of the doped GaAs and clean the surface after the contacts were annealed to the sample.

Samples were mounted in an MMR Technologies tabletop refrigerator, with a computer-controlled temperature controller. Current for the noise measurements was supplied by a battery in series with a wire-wound resistor; voltages were amplified with a Princeton Applied Research 113 amplifier. Data were taken with an LSI11/23 microcomputer equipped with a SKYMNK array processor, an ADAC analog-to-digital converter, and computer-switchable antialias filters made by Frequency Devices. This system, as described previously,¹⁰ allows the measurement not only of power spectra but of other statistical properties as well.

The power spectrum was computed from a series of 1024-point Fourier transforms. These were summed by

comes from noise power fluctuations on a much slower time scale than the inverse of the noise frequency.¹⁰ The extra variance in noise power was usually almost independent of the frequency for the same number of bins/octave. In one case however, an increase in the variance at high frequencies corresponded to a decrease in the noise power occurring at the same frequency, and both the feature in the variance and the feature in the power spectrum itself had the same temperature dependence.

In all cases, the noise was still non-Gaussian after re-exposure to air. To investigate the sensitivity of these non-Gaussian effects to surface conditions, sample No. 3 was then treated by painting a film of Duco cement diluted in acetone over the noise-generating region. This did not have a large effect on the non-Gaussian effects. Cleaning the sample with methanol increased the noise magnitude, especially at lower frequencies (see Fig. 1). This larger noise magnitude was much closer to Gaussian, but the higher frequency bands still exhibited the slow power modulations. All these results are consistent with the presence of a highly non-Gaussian approximately 1/f component, together with remnants of the Gaussian discrete components.

Second spectra were taken on this non-Gaussian noise after several different surface treatments which preserved the large non-Gaussian effects. The second spectra show that the low-frequency power modulation responsible for the increased variance of the noise power has a power spectrum approximately 1/f itself (see Fig. 2), with a small white component about 0.1 as large as the Gaussian variance.

The white component is more easily measured in lower frequency parts of the first spectrum than those shown in Fig. 2, for reasons having to do with the system processing

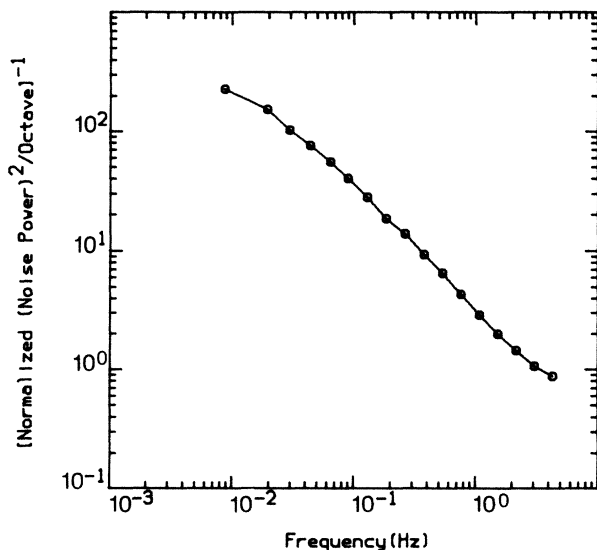


FIG. 2. Second spectrum taken on the noise in an octave band centered at 10 kHz in GaAs sample No. 2. The Gaussian prediction of 1.0 has been subtracted. The 1/f form of the spectrum was stable in time, and did not depend on which sample was looked at nor on which octave of the ordinary spectrum was chosen for analysis.

speed. Actual values varied from 0.0 to 0.2 of the Gaussian value. Such a component, with variations of roughly that magnitude, is expected for noise arising from a superposition of random two-state systems.¹¹ We can estimate the density of such systems (which have a distribution both of characteristic frequencies for their Lorentzian spectra and of duty cycles) contributing to the noise at any time to be about 0.4 per (factor of e in characteristic frequency \times factor of e in ratio of on to off times). The noise magnitude is consistent with such a density of electron traps, and would not be consistent with that density of two-state systems for transitions having much less effect on the conductivity than electron trapping.

The large 1/f modulation of the noise power is not consistent with a simple superposition of two-state systems. This intriguing result could arise from a number of sources, including fluctuations in some single degree of freedom affecting the noise at all frequencies in the same way, such as amplifier gain or effective sample size, which depends on surface potential. We checked this possibility by looking at the off-diagonal terms of the covariance matrix, the correlation coefficients for the noise in different octave bands.

The correlation coefficients $r(i, j)$ for the power fluctuations in the i th and j th octaves are well defined regardless of the detailed statistical properties of the noise. When, however, each octave shows variance well in excess of the Gaussian value we can compute another useful correlation parameter

$$r'(i, j) = r(i, j) [\psi(i) \psi(j)]^{1/2} / \{[\psi(i) - 1][\psi(j) - 1]\}^{1/2},$$

where $\psi(i)$ is the variance for octave i , normalized so that Gaussian noise gives 1. The r' values are, roughly, the correlation coefficients for the excess variance whose origin is being sought. Table I shows the covariance matrix for sample No. 3 with the off-diagonal terms being the $r'(i, j)$ and the diagonal terms being $\psi(i)$. The small values of $r'(i, j)$ for nonadjacent octaves show that the excess noise variance in the different octaves is not completely correlated. We checked the calibration of the system by measuring a similar matrix on an otherwise Gaussian noise source for which the amplifier gain was twiddled; the resulting values of r' ranged from 0.94 to 0.99.

Thus the extra variance is definitely not due to some overall drift in sample properties which has a similar effect on different fluctuating sites. The 1/f spectrum of this extra variance would not result from drift (which gives 1/f²) anyway.

Another possibility would be that the spectrum consisted of superposed Lorentzians from carrier traps, but with some amplitude modulation of each trap's noise as the Fermi level in its vicinity drifted up and down, for unspecified reasons. Such a model would give a well-defined prediction for how the $r'(i, j)$ fall off for $i \neq j$. The results in Table I are very close to that prediction, as shown in Fig. 3. It is extremely unlikely for several reasons that the Fermi-level changes could be due to overall samples drifts. The large magnitude of the non-Gaussian effects would require fluctuations in the Fermi level more about two orders of magnitude larger than could have been present for the samples which showed mainly discrete noise components.

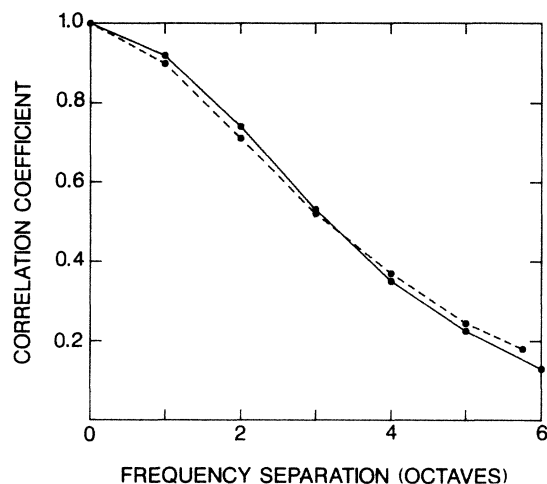


FIG. 3. The solid line connects points for the predicted correlation coefficient of the non-Gaussian variance of the noise in different octaves computed on the assumption that the noise arises from Lorentzians with a $1/f$ distribution of characteristic rates, each of which has an independently modulated amplitude. The dashed line is taken from the average of off-diagonal terms in Table I. Similar data were consistently found on the other sample, after several months sitting in ambient atmosphere, and in other frequency ranges. There are no adjustable parameters in this plot.

Furthermore, we would be unable to explain why the samples with larger remnants of the discrete components show smaller non-Gaussian effects precisely in those regions of the spectrum known to be affected by the average surface potential. The reproducibility of the magnitude of the effects in similarly treated samples would not fit well with such an explanation.

The relative magnitudes of the $1/f$ and white portions of the second spectrum provide further information. If we

assume that the white part of the excess second spectrum is of about the same size as is obtained for a static ensemble of two-state systems with random times and duty cycles, and that the $1/f$ part results from a modulation of the intensity from each site, we find that the mean-square fractional modulation is of order unity. Thus it appears that each site is somehow turned off and unable to fluctuate for half or more of the time. The noise source is not even approximately a superposition of static, independent two-state systems.

If some form of series kinetics were involved, however, the $1/f$ second spectrum and the covariance matrix might make sense. If the ability of some fluctuating element to contribute to the noise in a given frequency range could be turned on or off by neighboring elements, as in some kinetic Ising models,^{6,7} it would show noise power fluctuations with characteristic times typical of neighboring slower elements. The effect of neighboring elements with faster times would only be to renormalize the bare time of a single site. Thus the similarity of the second spectrum to the spectrum itself would not be fortuitous.

However, the close agreement between the interoctave correlation coefficients and the prediction for independently modulated Lorentzians indicates that the bare times of the separate sites are themselves distributed, as in other $1/f$ systems.¹¹ That agreement would be very hard to obtain if each site had a range of characteristic times induced by the intersite coupling. It is highly suggestive that in small metal-insulator-metal junctions, trapping transitions which are mutually exclusive are occasionally directly observed.¹³

This work was supported by the National Science Foundation under Grant No. DMR83-04470 and by facility usage at the Material Research Laboratory under National Science Foundation Grant No. DMR 83-16981. P. J. Restle was supported by the IBM corporation.

¹F. K. Du Pre, *Phys. Rev.* **79**, 615 (1950).

²A. Van der Ziel, *Physica* **16**, 359 (1950).

³P. Dutta and P. M. Horn, *Rev. Mod. Phys.* **53**, 497 (1981).

⁴A. K. Jonscher, *Nature* **267**, 673 (1977).

⁵E. Marinari, G. Parisi, D. Ruelle, and P. Windey, *Commun. Math. Phys.* **89**, 1 (1982).

⁶R. J. Palmer, D. L. Stein, E. Abrahams, and P. W. Anderson, *Phys. Rev. Lett.* **53**, 958 (1984).

⁷G. H. Frederickson and H. A. Andersen, *Phys. Rev. Lett.* **53**, 1244 (1984).

⁸K. S. Ralls, W. J. Skocpol, L. D. Jaeckel, R. E. Howard, L. A.

Fetter, R. W. Epworth, and D. M. Tennant, *Phys. Rev. Lett.* **52**, 228 (1984).

⁹C. T. Rogers and R. A. Buhrman, *Phys. Rev. Lett.* **53**, 1272 (1984).

¹⁰P. J. Restle, M. B. Weissman, and R. D. Black, *J. Appl. Phys.* **54**, 5844 (1983).

¹¹P. J. Restle, R. J. Hamilton, M. B. Weissman, and M. S. Love, *Phys. Rev. B* **31**, 2254 (1985).

¹²P. J. Restle, Dissertation, University of Illinois, 1985 (unpublished).

¹³C. T. Rogers, *Bull. Am. Phys. Soc.* **31**, 536 (1986).